



Recent progress in fundamental surface science for improved plasma performance in NSTX-U

Bruce E. Koel, <u>Luxherta Buzi</u>, Oluseyi Fasoranti, and Xiaofang Yang

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Fundamental surface science of PFCs for improved plasma performance in NSTX-U

Goal 1: Deeper understanding of how boron and lithium affect the performance of NSTX-U

Goal 2: Develop predictive basis of how Li, Sn, or Li/Sn will perform under the plasma conditions of future fusion devices such as FNSF-ST with increased heat and particle flux, ion energy, surface temperature, etc. in terms of:

- H isotope intake
- Impurity segregation
- Evaporation (operational temperature range)?

Deepen understanding of PMI processes by measuring:

- D retention in Li films as a function of impurity level (C, O) and surface temperature (on Mo substrates)
- Boron and Lithium conditioned plasmas performance, D retention and surface chemistry in Mo-B-O-C and Mo-Li-O-C layers: a comparison with MAPP results
- Diffusion coefficient of O in Li and its temperature dependence; developing strategies for the removal of contaminants
- Li and Sn wetting of TZM; Investigations with TPD to determine Li-Mo and Sn-Mo adhesion energies
- Composition and surface chemistry of Sn and Sn-Li alloys for alternative PFC solutions
 - Thermally induced segregation mechanisms of Sn-Li alloys
 - D retention in Sn and Sn-Li alloys
- D⁺ sputtering coefficients of Li and Li-C-O layers

Interpretation of MAPP results and surface spectroscopy to complement MAPP analysis

- Working closely with Felipe Bedoya (also Hanna Schamis) to interpret MAPP XPS results, e.g., meeting Felipe 2X/week for long sessions of instruction and assistance.
- Samples taken for additional spectroscopic characterization and surface science studies to SSTL after removal from MAPP, e.g. HR-XPS to benchmark determination of chemical states present in samples.









Thermal stability of Li on Mo(poly) and TZM



 Surface composition studies show that Oxygen increases from 300-900 K due to diffusion from the bulk or oxidation from background





Thermal stability of Li and Sn on high-Z plasma facing materials

- Both thick Sn films and the Sn/Mo monolayer are more thermally stable by about 600 K than the corresponding Li films, *e.g. complete Sn evaporation from TZM does not occur until 1700 K.*
- Oxygen impurities affect the thermal stability of Li and Sn films profoundly differently, e.g. Li stability is increased due to oxidation by 400 K, while Sn stability is decreased by 200 K



Chemical and physical erosion and implantation measurements for low energy ions

- Reconfiguration and upgrading of versatile instrument for mass and velocity filtered ion scattering measurements using Colutron ion source, *e.g. should now be possible to investigate surface processes of incident ions with energies of a few eV.*
- Successful installation of Model 400 deceleration lens consisting of six electrically insulated concentric cylinders mounted at the exit of the Colutron ion source.
- Renovation of a Comstock cylindrical sector electrostatic analyzer underway to enable forward-scattering detection of surface-bound hydrogen.



Backup slides

Oxygen impurities affect the thermal stability of Li





- TPD shows 3 Peaks at 820 K, 1000 K and 1200 K after 20 L oxidation of Li on TZM
- XPS shows new binding states for oxygen as the film is annealed to different temperatures

Thermal stability of Li increased on pre-oxidized TZM



- Oxygen saturation of the top layer of TZM occurs after 2 L of O₂ Exposure as shown by ISS
- Increased thermal stability of Li on O-TZM